Sensors and Materials, Vol. 26, No. 4 (2014) 245–251 MYU Tokyo

S & M 0988

Mid-infrared Type-II InAs/GaSb Superlattice Photodiodes Fabricated on InP Substrates

Kohei Miura^{*}, Yasuhiro Iguchi, Tsukuru Katsuyama, Yuichi Kawamura¹, Junpei Murooka², Haruyoshi Katayama², Shota Sugano³, Tomoko Takekawa³ and Masafumi Kimata³

Transmission Devices R&D Laboratories, Sumitomo Electric Industries, Ltd., 1, Taya-cho, Sakae-ku, Yokohama, Kanagawa 244-8588, Japan ¹Graduate School of Engineering, Osaka Prefecture University, 1-2 Gakuen-cho, Naka-ku, Sakai, Osaka 599-8570, Japan
²Earth Observation Research Center, Japan Aerospace Exploration Agency, 2-1-1 Sengen Tsukuba, Ibaraki 305-0035, Japan
³Graduate School of Science and Engineering, Ritsumeikan University, 1-1-1 Noji-higashi, Kusatsu, Shiga 525-8577, Japan

(Received November 28, 2013; accepted February 17, 2014)

Key words: GaSb, InAs, type-II superlattice, InP, mid-infrared photodiode

Type-II InAs/GaSb superlattices (SLs) are attractive material systems for mid-infrared photodiodes (PDs) with higher detectivities than the conventional HgCdTe. GaSb substrates are generally used for the epitaxial growth of these type-II SLs. However, in the case of back-illuminated PDs, the GaSb substrate should be nearly removed because of its strong absorption of mid-infrared light. In this study, infrared PDs with a cut-off wavelength of 7 μ m were fabricated for the first time by using the 100 period of InAs/GaSb SLs grown on an InP substrate, which has much less absorption of mid-infrared light. The dark current density at the reverse bias of -0.1 V and at a temperature of 112 K was 33.0 mA/cm². External quantum efficiency over 10% at the wavelength of 5 μ m was obtained.

*Corresponding author: e-mail: miura-kouhei@sei.co.jp